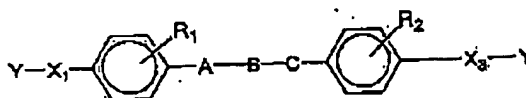


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Amendments to the Claims:

Claims 1 – 14 (Cancelled)

15. (Currently Amended) A photosensitive composition for optical waveguides comprising an organic oligomer and a polymerization initiator, said organic oligomer being an oligomer represented by the following formula (5a):



(5a)

wherein R<sub>1</sub> and R<sub>2</sub> may be the same as or different from each other, and denote hydrogen, halogen, an alkyl group, an alkoxy group or a trifluoromethyl group; X<sub>1</sub> and X<sub>3</sub> may be the same as or different from each other, and denotes a connection group including at least one selected from the group consisting of an alkyleneoxy and oxyalkylene group; X<sub>3</sub> is selected from the group consisting of an oxyalkylene group and an alkyleneoxy group; Y denotes a polymerization activating group containing acrylic or methacrylic group and A denotes a connection group selected from a linear or branched alkylene group; B denotes a connection group selected from the group consisting of a substituted or an unsubstituted phenylene; C denotes a connection group selected from alkyleneoxy.

16. (Canceled)

17. (Original) A method of forming a polymer optical waveguide pattern, comprising the steps of:

applying and drying a photosensitive composition for optical waveguides;  
 irradiating said resultant photosensitive composition thin film for optical waveguides with light through a mask; and

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directly forming a core-ridge pattern by wet etching said photosensitive composition thin film;

wherein the photosensitive composition for optical waveguides as claimed in Claim 15 is used as said photosensitive composition for optical waveguides.

Claims 18-30 (Cancelled)